

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Maruyama et al.
Appl. No.	:	10/522,036
Filed	:	January 19, 2005
For	:	CHEMICAL AMPLIFICATION TYPE POSITIVE PHOTORESIST COMPOSITION AND RESIST PATTERN FORMING METHOD
Examiner	:	Lee, Sin J
Group Art Unit	:	1752

AMENDMENT AND RESPONSE TO FINAL OFFICE ACTION**Mail Stop AF**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **September 15, 2006**, please consider the following amendments and remarks.

Amendments to the claims begin on page 2 of this paper.

Remarks/Arguments begin on page 13 of this paper.